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(54) DEVICE AND METHOD FOR DEVELOPING

(57) Abstract

PROBLEM TO BE SOLVED: To provide an developing device and method for improving the uniformity of pattern line width after development.

SOLUTION: A developer jet nozzle 11 having a slit-shaped jet port is moved from one side position outside a substrate 100 held by a substrate holding part 1 in a static state through the substrate 100 to the other side position outside the substrate 100, and developer is supplied to the substrate 100. The substrate 100 held by the substrate holding part 1 is rotated the prescribed number of times after the lapse of a prescribed time since the end of the supply of the developer to the substrate 100 by the developer jet nozzle 11, and then the substrate 100 is held in a static state in a prescribed time by the substrate holding part 100. The rotation of the substrate 100 and the holding of the substrate 100 in the static state is repeated the prescribed number of times.

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